

Substitute for ~~Information Disclosure Statement~~**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Sheet

1

of

2

Complete if Known

Application Number	10/581,622
Date Filed:	June 5, 2006
First Named Inventor	David FORREST
Group Art Unit	1774
Examiner Name	

Attorney Docket Number 52993/326894

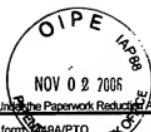
U.S. PATENT DOCUMENTS

Examiner Initials + Name	Cite No. ¹	Document Number Number - Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
/LF/		US-4,997,678	03/05/1991	Taylor, et al.	
/LF/		US-5,098,631	03/24/1992	Pyzik, et al.	
/LF/		US-5,504,151	02/18/1997	Goela, et al.	
/LF/		US-5,612,132	03/18/1997	Goela, et al.	
/LF/		US-6,042,758	03/28/2000	Goela	
/LF/		US-6,228,297	05/08/2001	Goela, et al.	
/LF/		US-6,231,923	05/15/2001	Teverovsky, et al.	
/LF/		US-6,464,912	10/15/2002	Goela, et al.	
/LF/		US-20010022408 A1	09/20/2001	Goela, et al.	
/LF/		US-20020004444 A1	01/10/2002	Goela, et al.	
/LF/		US-2003036471 A1	02-20-2003	Goela	
/LF/		US-2005/0123713 A1	06-09-2005	Forrest	

FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No. ¹	Foreign Patent Document Country Code ³ - Number ⁴ - Kind Code ⁵ (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
/LF/		E P 1 127955 A1	08-29-2001	Shipley Company LLC		
/LF/		EP 0 955 278 A2	11-10-1999	CVD Incorporated		
/LF/		EP 0 588 479 A1	03-23-1994	CVD Incorporated		
/LF/		WO 99/41773	08-19-1999	Applied Materials, Inc.		

Examiner Signature	/Lawrence Ferguson/	Date Considered	07/31/2008
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.			



NOV 02 2006

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

PTO/SB/08A (10-01)

Van Zile, et al. Approved for use through 10/31/2002. OMB 0651-0031
U.S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE

Substitute for form 1-19A/PTO

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(use as many sheets as necessary)

She

10

1

1

Complete if Known

Application Number	10/581,622
Date Filed:	June 5, 2006
First Named Inventor	David FORREST
Group Art Unit	1774
Examiner Name	
Attorney Docket Number	52993/326894

OTHER PRIOR ART – NON-PATENT LITERATURE DOCUMENTS

OTHER PRIOR ART - NON-PATENT LITERATURE DOCUMENTS			
Examiner Initials *	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
/LF/	Collins, et al., 'Investigation of CVD β -SiC Surfaces Produced via a 'Novel' Surface Replication Process,' <i>Mat. Res. Soc. Symp. Proc.</i> , 168:193-198 (1990)	
/LF/	Collins, et al., 'Grain size dependence of the thermal conductivity of polycrystalline chemical vapor deposited β -SiC at low temperature,' <i>J. Appl. Phys.</i> , 68(12):6510-6512 (1990)	
/LF/	Goela and Taylor, 'Chemical Vapor Deposition for Silicon Cladding on Advanced Ceramics,' <i>J. Am. Ceram. Soc.</i> , 72(9):1747-1750 (1989)	
/LF/	Kim and Zangvil, 'Microstructure Comparison of Transparent and Opaque CVD SiC,' <i>J. Am. Ceram. Soc.</i> , 78(6):1571-1579 (1995)	
/LF/	Qadri, et al., 'Characteristics of Plasma Processed SiC Nanocrystallites and Nanorods,' <i>Applied Physics Letters, American Institute of Physics</i> , 83(3):546-550 (July 21, 2003)	

Examiner Signature	/Lawrence Ferguson/	Date Considered	07/31/2008
-----------------------	---------------------	--------------------	------------